

IN THE CLAIMS AMEND

1. (Cancelled)
2. (Currently Amended) A projection printing installation as claimed in claim 15, wherein a throttle valve ~~(23)~~ is disposed in at least one supply line ~~(21)~~ for the gas nozzle ~~(11)~~.
3. (Currently Amended) A projection printing installation as claimed in claim 15, wherein the gas nozzle is formed by at least one nozzle ~~(11)~~, which is connected by the supply line ~~(21)~~ to a gas source ~~(22)~~.
4. (Currently Amended) A projection printing installation as claimed in claim 15, wherein a plurality of gas nozzles ~~(11)~~ are provided, with each of which a throttle valve ~~(20)~~ in a supply line section ~~(19)~~ is associated.
5. (Cancelled)
6. (Currently Amended) A microlithographic projection printing installation having a rotationally non-symmetrical illumination and comprising a light source which emits radiation, an optical element which is heated by the radiation, and a supply apparatus for tempering the optical element, wherein the supply apparatus comprises at least one supply line and at least one gas nozzle for directing a gas flow onto the optical element, and an adjustable holder for the gas nozzle, wherein the holder comprises an adjusting device for adjusting the axial position of the gas ~~directing device~~ nozzle ~~(11)~~ relative to the optical element.
7. (Previously Amended) A microlithographic projection printing installation having a rotationally non-symmetrical illumination and comprising a light source which emits radiation, an optical element which is heated by the radiation, and a supply

apparatus for tempering the optical element, wherein the supply apparatus comprises at least one supply line and at least one gas nozzle for directing a gas flow onto the optical element, and an adjustable holder for the gas nozzle, wherein the holder comprises an adjusting device for adjusting the inclination of the gas nozzle relative to the optical element.

8. (Currently Amended) A projection printing installation as claims in claim 2, wherein there is a control device ~~(25)~~ with a communication link to the at least one throttle valve ~~(20, 23)~~ for selecting a volumetric flow of gas in the gas nozzle (11).

9. (Currently Amended) A projection printing installation as claimed in claim 8, wherein the control device ~~(25)~~ has a communication link ~~(27, 28, A)~~ to the light source ~~(2)~~ for receiving a signal corresponding to the light output of the light source, wherein the selection of the volumetric flow of a gas is effected by the control device ~~(25)~~ in dependence upon the transmitted signal of the light source ~~(2)~~.

10. (Currently Amended) A projection printing installation as claimed in claim 8, wherein there is a sensor arrangement ~~(31)~~ with a communication link ~~(27, 28, 30)~~ to the control device ~~(25)~~ for monitoring the imaging quality of the optical element ~~(5)~~ and/or of the optical arrangement ~~(4, 5)~~, wherein the selection of the volumetric flow of gas is effected by the control device ~~(25)~~ in dependence upon the transmitted signal data of the sensor arrangement ~~(31)~~.

11. (Currently Amended) A projection printing installation as claimed in claim 10, wherein the sensor arrangement comprises a CCD array ~~(31)~~.

12. (Currently Amended) A projection printing installation as claimed in claim 15, wherein the gas nozzle ~~(11)~~ is part of a sweeping device for the optical element ~~(5)~~.

13. (Currently Amended) A projection printing installation as claimed in claim 15, wherein there is a thermostatted tempering device ~~(24)~~ in the supply line ~~(21)~~.

14. (Currently Amended) A projection printing installation as claimed in claim 15, wherein the gas nozzle ~~(11)~~ is part of a sweeping device for the projection printing installation ~~(4, 5)~~.

15. (Previously Amended) A microlithographic projection printing installation having a rotationally non-symmetrical illumination and comprising a light source which emits radiation, an optical element which is heated by the radiation, and a supply apparatus for gas tempering the optical element, wherein the supply apparatus comprises at least one gas supply line and at least one gas nozzle for directing a gas flow onto the optical element, the gas nozzle being held by a holder that comprises an adjusting device for changing the spatial position of the gas nozzle relative to the optical element.

16. (Previously Added) A microlithographic projection printing installation having a rotationally non-symmetrical illumination and comprising a light source which emits radiation, an optical element which is heated by the radiation, and a supply apparatus for gas tempering the optical element, wherein the supply apparatus comprises at least one gas supply line and at least one gas nozzle for directing a gas flow onto an impingement zone of the optical element, the gas nozzle being held by a holder that comprises an adjusting device for altering the location of the impingement zone on the optical element.